

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Kouji Fujiyoshi et al.)	Group Art Unit
Serial No.	:	New Application)	
Filed	:	Concurrently Herewith)	
For	:	ELECTRON BEAM EXPOSURE)	
		APPARATUS, ELECTRON BEAM)	
		EXPOSING METHOD,)	
		SEMICONDUCTOR ELEMENT)	
		MANUFACTURING METHOD, AND)	
		PATTERN ERROR DETECTION)	
		METHOD)	
Examiner	:	Unknown)	

INFORMATION DISCLOSURE STATEMENT

Hon. Commissioner
of Patents and Trademarks
Washington, D.C. 20231

Dear Sir:

Enclosed is a form PTO-1449 listing five prior art references relevant to the above-identified application. A copy of the five references and English abstracts is also enclosed herewith.

These prior art references are cited in the International Search Report issued by Japanese Patent Office in the international stage of this case. A copy of the English version of International Search Report is also attached herewith. Since all of the prior art references are non-English documents, an English abstract is attached to each of the references. The prior art references enclosed are:

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(1) Japanese Patent Laid-Open Publication No. 07-235477 is relevant to the present invention because it discloses a process of radiating electron beam on a semiconductor integrate circuit device.

(2) Japanese Patent Laid-Open Publication No. 07-192985 is relevant to the present invention because it discloses a method and apparatus for forming patterns by exposing electron beams on a specimen.

(3) Japanese Patent Laid-Open Publication No. 05-190435 is relevant to the present invention because it discloses an electron beam lithography method of semiconductor device for drawing a pattern thereon.

(4) Japanese Patent Laid-Open Publication No. 08-279450 is relevant to the present invention because it discloses a charged particle beam exposing method and apparatus for forming a pattern on a semiconductor device.

(5) Japanese Patent Laid-Open Publication No. 60-009121 is relevant to the present invention because it discloses a method of evaluating a pattern data involved in an electron beam exposing apparatus for forming a pattern on a semiconductor device.

Applicant respectfully requests that the prior art references submitted be considered in the substantive examination of this application.

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Respectfully submitted,

MURAMATSU & ASSOCIATES

Dated: 11/12/2003

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Substitute for form 1449A/PTO		Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>		Application Number	
		Filing Date	11/12/2003
		First Named Inventor	Kouji Fujiyo Shii
		Group Art Unit	
		Examiner Name	
Sheet	1	of	1
		Attorney Docket Number	RYUKA. 802 AUS

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

Examiner Signature		Date Considered	
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

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